

FORMING A TRANSPARENT WINDOW IN A POLISHING PAD
FOR A CHEMICAL MECHANICAL POLISHING APPARATUS

ABSTRACT OF THE DISCLOSURE

The polishing pad for a chemical mechanical
5 polishing apparatus, and a method of making the same. The
polishing pad has a covering layer with a polishing surface
and a backing layer which is adjacent to the platen. A
first opening in the covering layer with a first cross-
sectional area and a second opening in the backing layer
10 with a second, different cross-sectional area form an
aperture through the polishing pad. A substantially
transparent polyurethane plug is positioned in the aperture,
and an adhesive material fixes the plug in the aperture.

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